

# Plasma Chemistry Data Research for Plasma Applications

**Jung-Sik Yoon, DCPD members**

Data Center for Plasma Properties, Plasma Technology Research Center,  
National Fusion Research Institute, Daejeon 305-333, Korea

As interest has increased in the interaction between low-temperature plasmas and materials, the role of modeling and simulation of processing in plasma has become important in understanding the effects of charged particles and radicals in plasma applications. Thus in this presentation, we present the theoretical and experimental studies of electron impact cross section for plasma processing gas, such as plasma etching and deposition processes. Also, here the work conducted at the Data Center for Plasma Properties (DCPP) over last 7 years on the systematic synthesis and assessment of fundamental knowledge on low-energy electron interactions with plasma processing gases is briefly summarized and discussed.

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